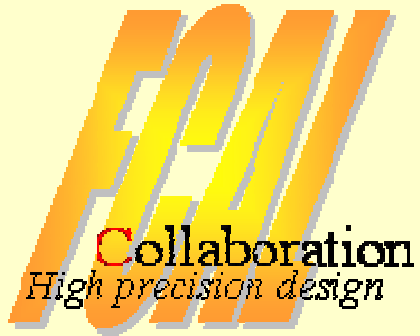


# Forward Region Instrumentation

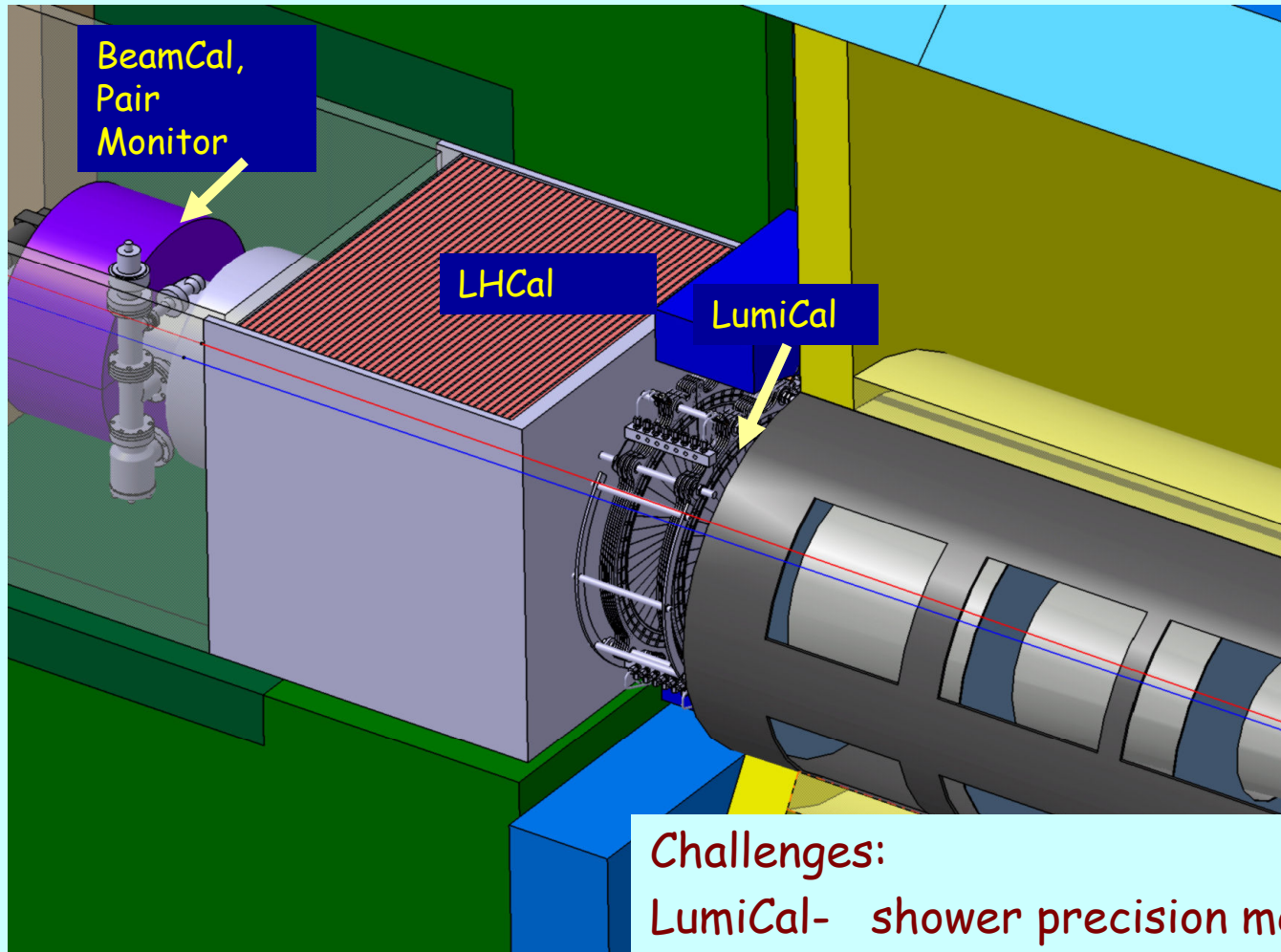


Wolfgang Lohmann

DESY

On behalf of the FCAL collaboration

# Forward Region, ILD Detector



## Challenges:

LumiCal- shower precision measurement

BeamCal - radiation hardness

Both - fast readout

## Recent Developments:

- Sensor Prototyping
- ASIC Development and Test
- System test

# BeamCal Sensors, GaAs

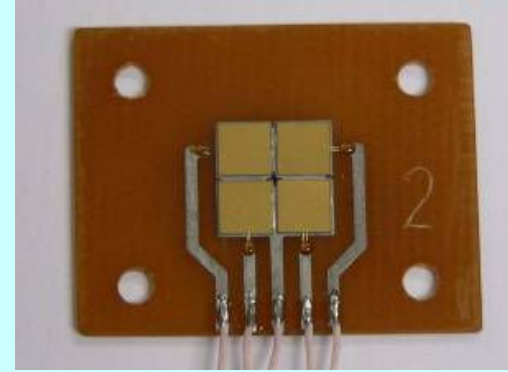
- n-type (Te or Sn - shallow donor) GaAs grown by Liquid Encapsulated Czochralski (LEC) method in Siberian Institute of Physics and Technology (Tomsk, Russia)
- low-ohmic material, filling the electron trapping centers EL2+
- Cr (deep acceptor) diffusion
- > high-ohmic

Thicknesses 150 - 200  $\mu\text{m}$

Metallization:

V (30 nm) + Au (1  $\mu\text{m}$ ) from both sides

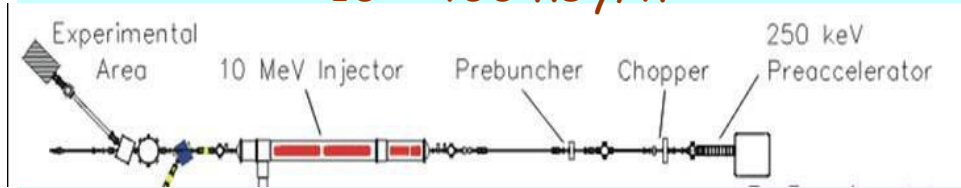
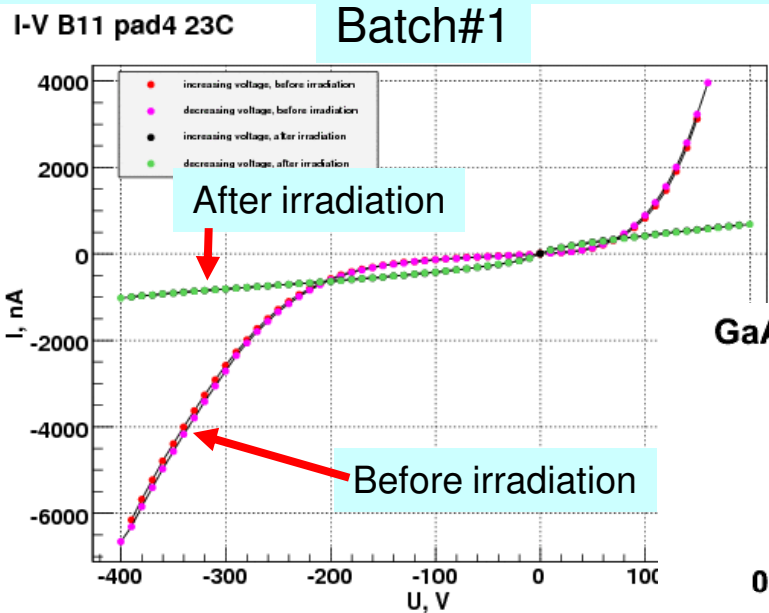
Irradiation in a 10 MeV electron beam, Doses up to 1.1 MGy



Initial n-GaAs	Fabrication method
№1, $n \approx (1 - 1.5) \cdot 10^{17} \text{ cm}^{-3}$ , Te	Diffusion of Cr under temperature T2
№2, $n \approx (5 - 6) \cdot 10^{16} \text{ cm}^{-3}$ , Te	Diffusion of Cr under temperature Tm
№3, $n \approx (1 - 3) \cdot 10^{16} \text{ cm}^{-3}$ , Sn	Diffusion of Cr under temperature T1
№4, $n \approx (2 - 5) \cdot 10^{16} \text{ cm}^{-3}$ , Te	p-v-n- structure*
Notice $T1 < Tm < T2$ .	
* - presence in the detector n- type low-resistance domain, all other detectors №1, 2, 3 had structure m-i-m: metal- insulator (high-resistance GaAs) –metal.	

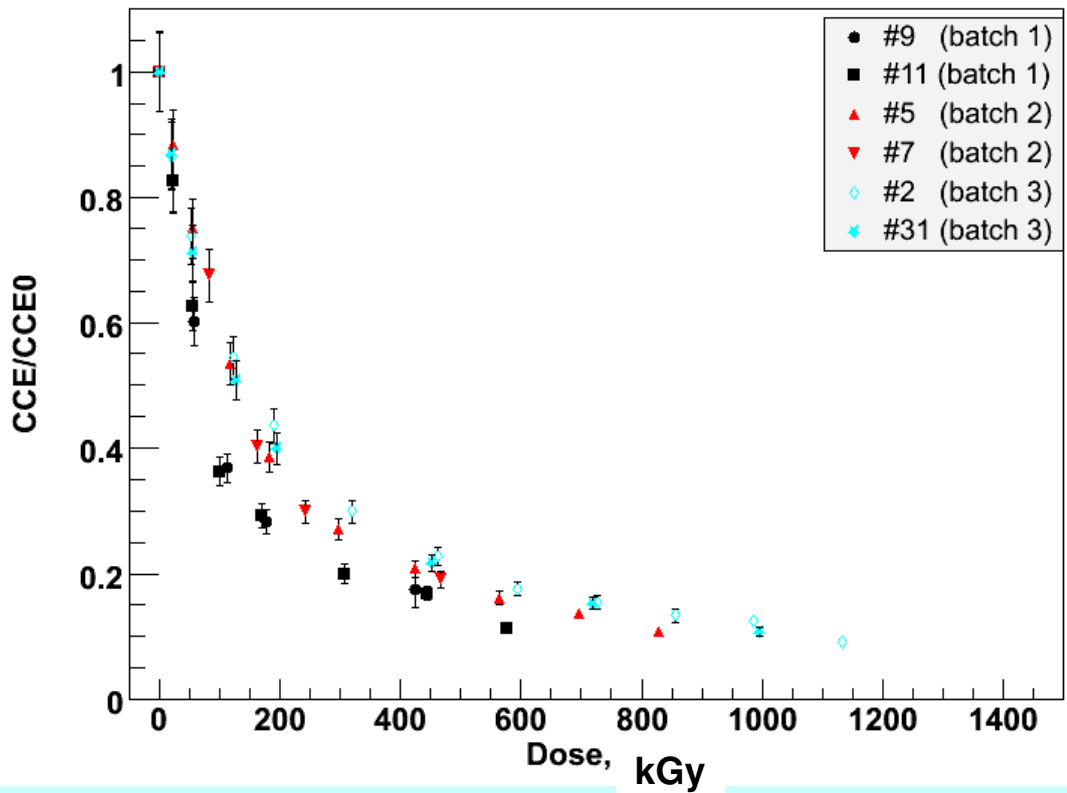
# BeamCal Sensors, GaAs

Irradiation with an 10 MeV electron beam (DALINAC, TU Darmstadt)



10 - 400 kGy/h

GaAs:Cr CCE vs dose

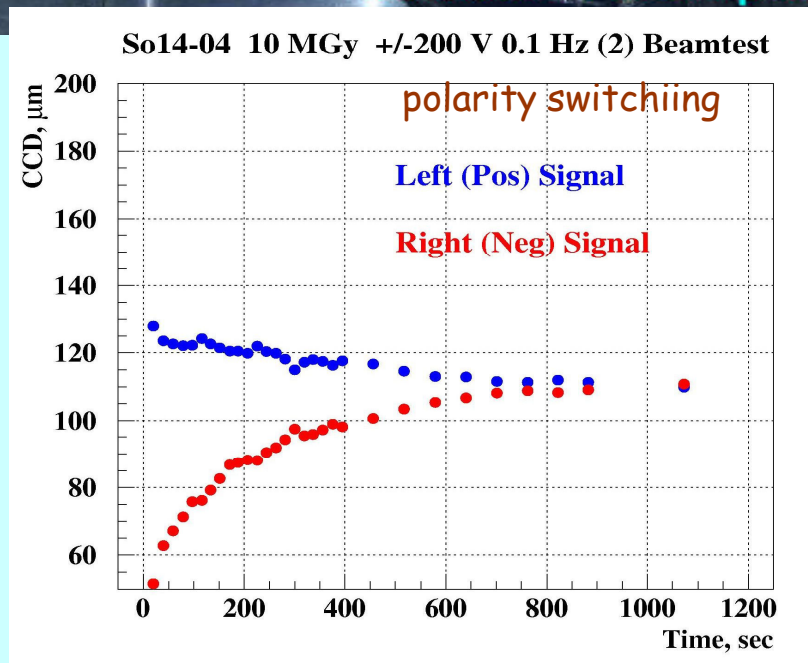
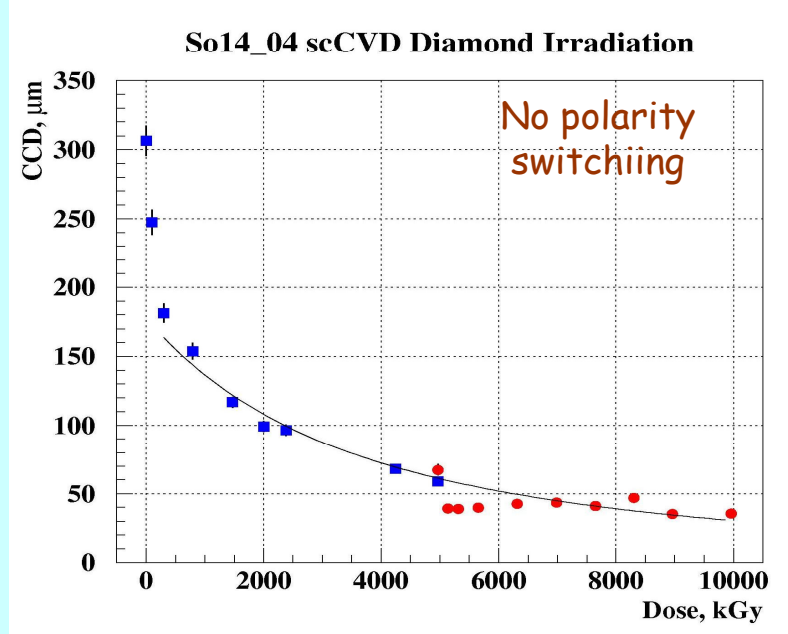
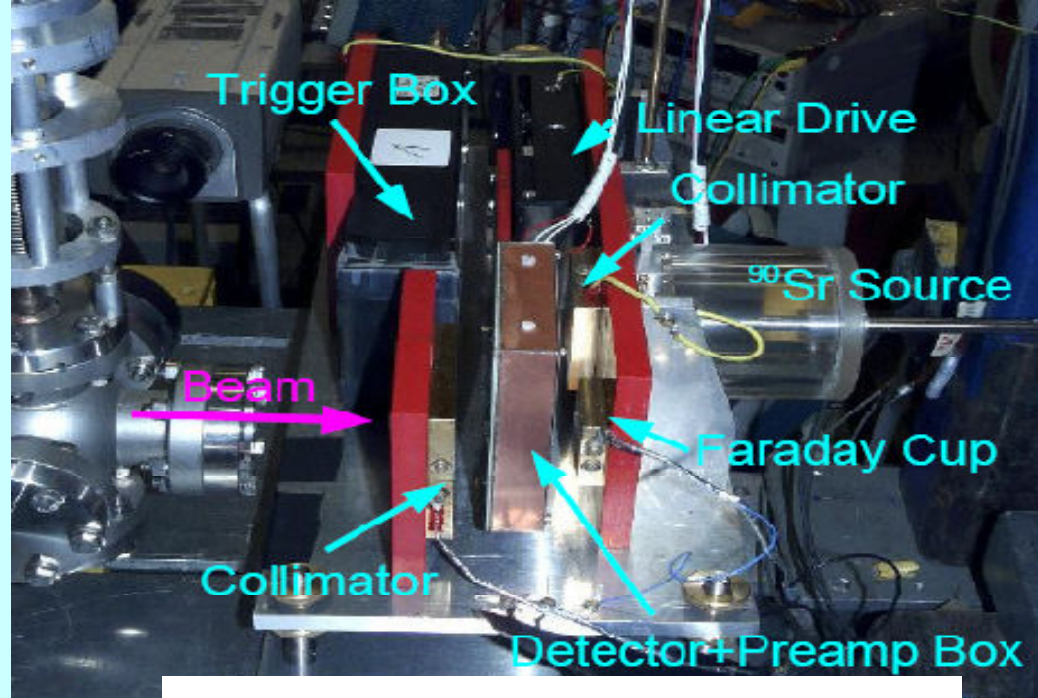


Up to 500 kGy a mip signal is clearly seen

Sensors with a lower concentration of shallow donor and Cr as deep acceptor show better rad. tolerance

# BeamCal Sensors, Diamond

sCVD diamond (E6), 5x5x0.3 mm<sup>3</sup>  
 Irradiated in 2007 up to 5 MGy  
 2008: up to 10 MGy  
 New set-up, for switching polarity during the measurement



# BeamCal Sensors, Sapphire

Band gap: 9.9 eV

(diamond: 5.5 eV, Si: 1.12 eV)

Single crystal, 1x1 cm<sup>2</sup>,  
cut 001

Wafer: 30 cm diameter)

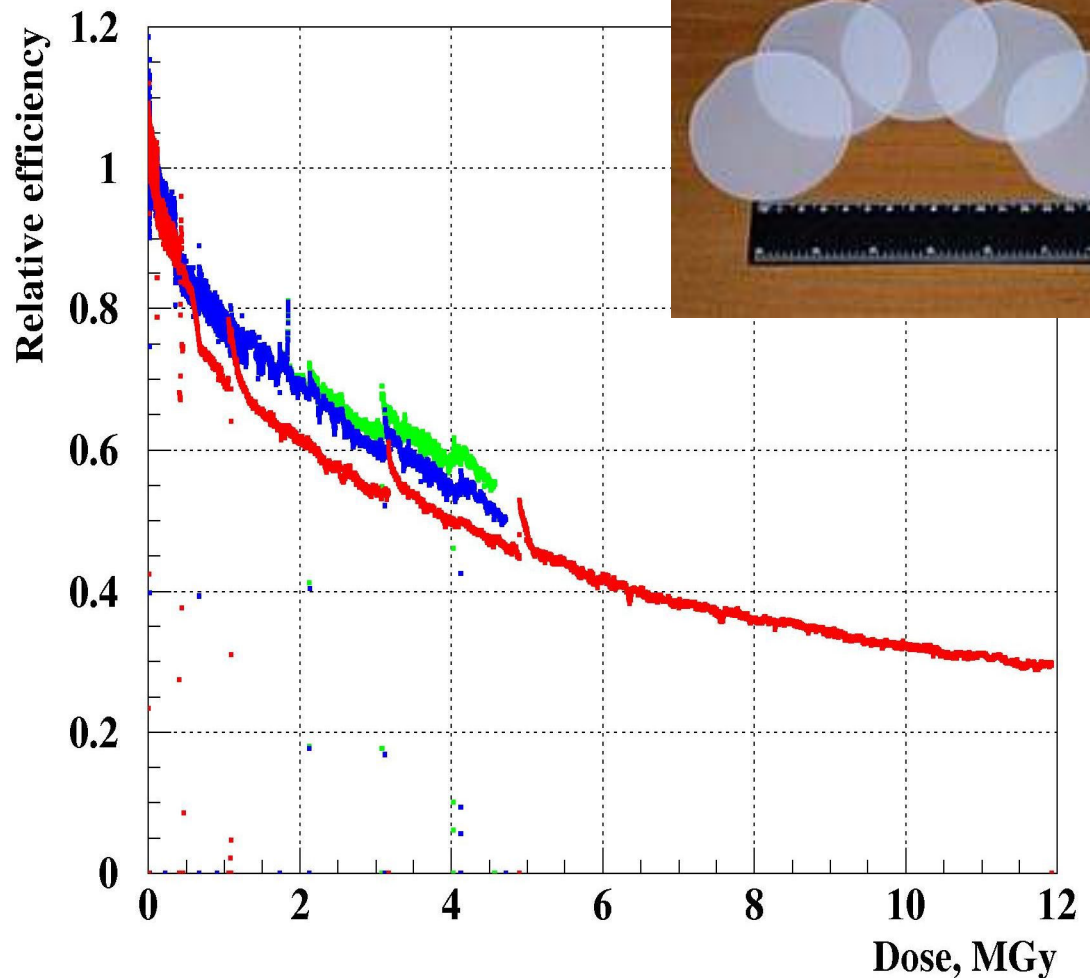
Metallisation:

50/50/200 nm Al/Ti/Au



Ratio of the detector and  
Faraday cup currents

## Sapphire Crb2 and C



Charge collection efficiency: few %

~ 30 % of the initial charge collection efficiency after 12 MGy

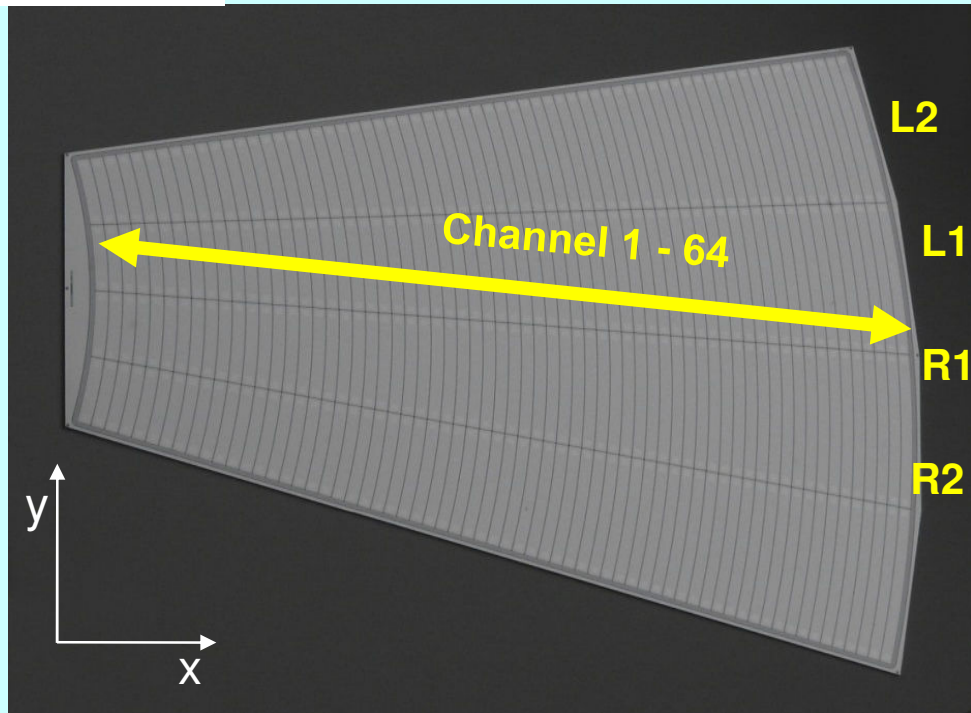
# Sensor prototypes (LumiCal)

## "Cracow-Design"

- High resistivity n-type Si
- 1,7mm p+ - strips with an Al-metallization
- Backplane: n+ implant and an Al-metallization
- 3 Guard rings

x-Size = 10,8cm  
y-Size = 4...12cm  
(6 Inch Wafers)

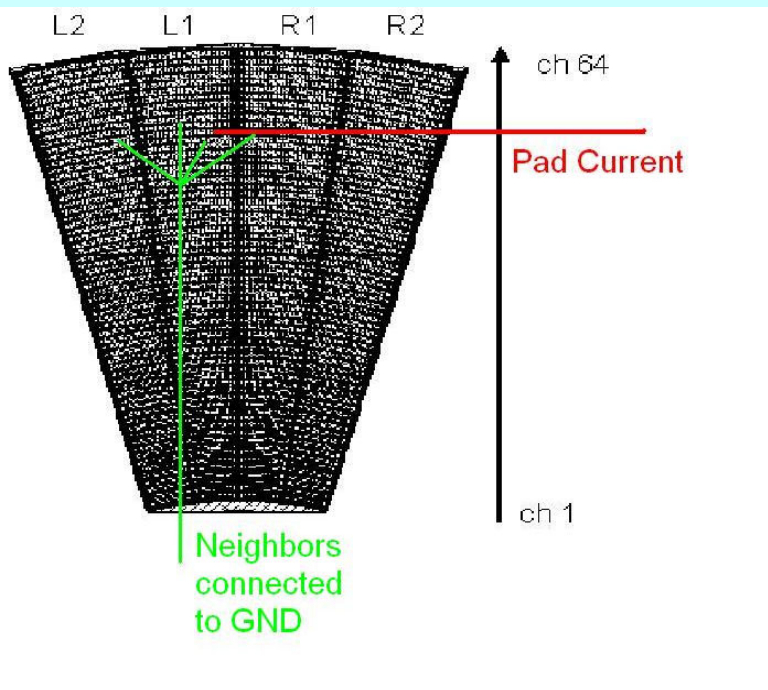
Hamamatsu  
S10938-8380



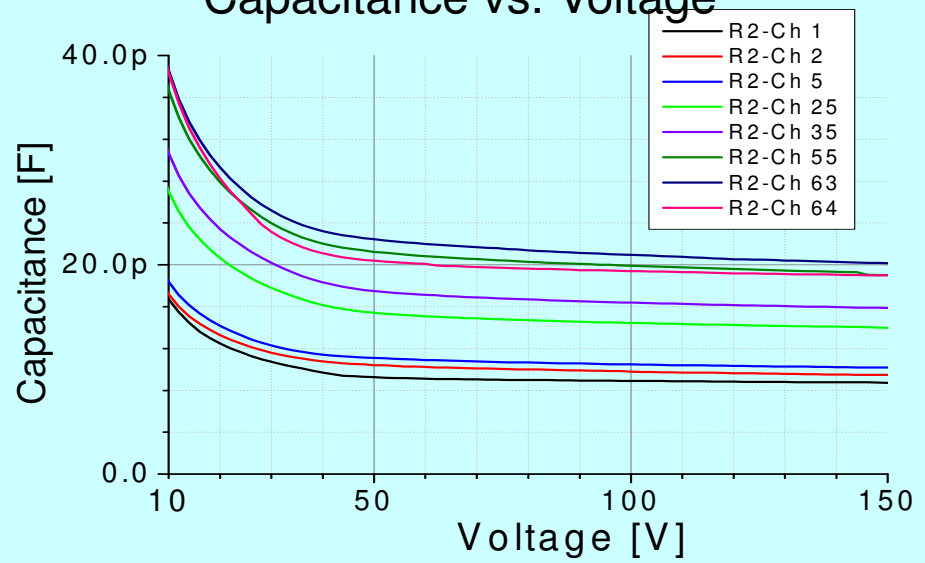
I(V) and C(V) measurements on Probe-  
stations in Tel Aviv, Cracow and DESY



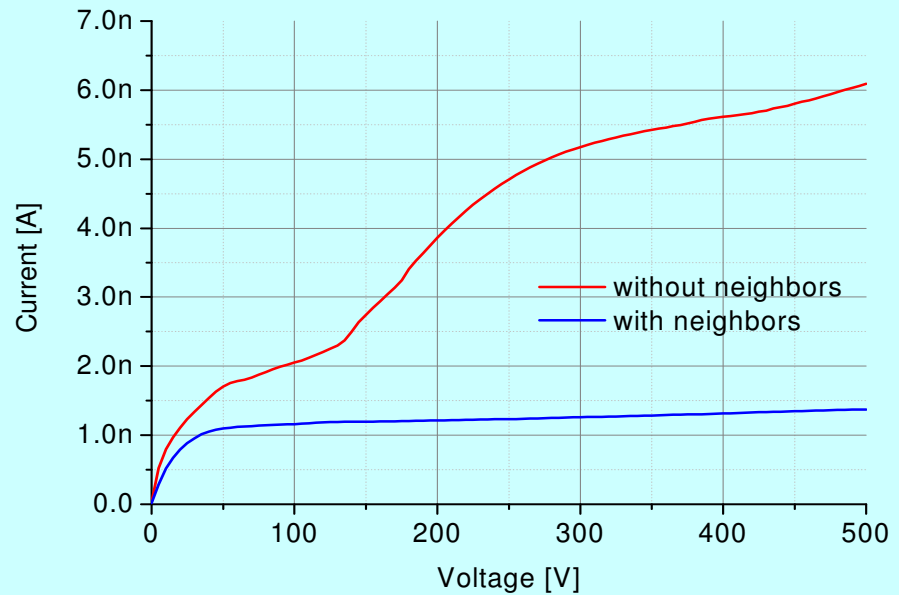
# Sensor prototypes (LumiCal)



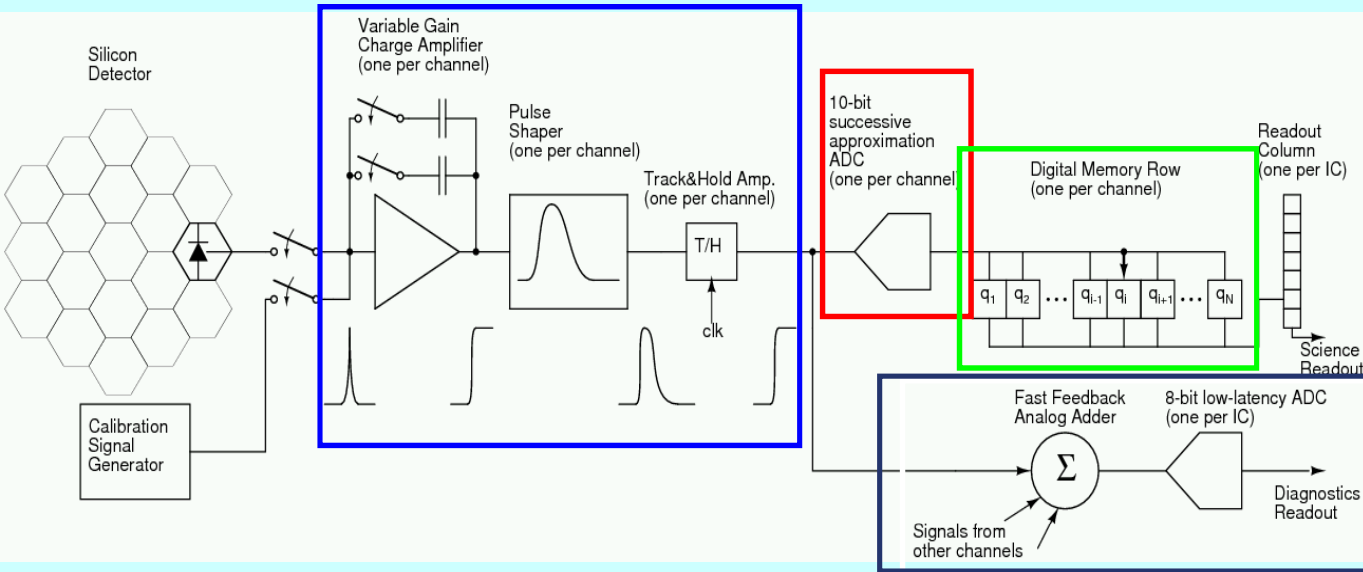
## Capacitance vs. Voltage



Serial No. 5 - R1 channel 30



# ASIC development, BeamCal

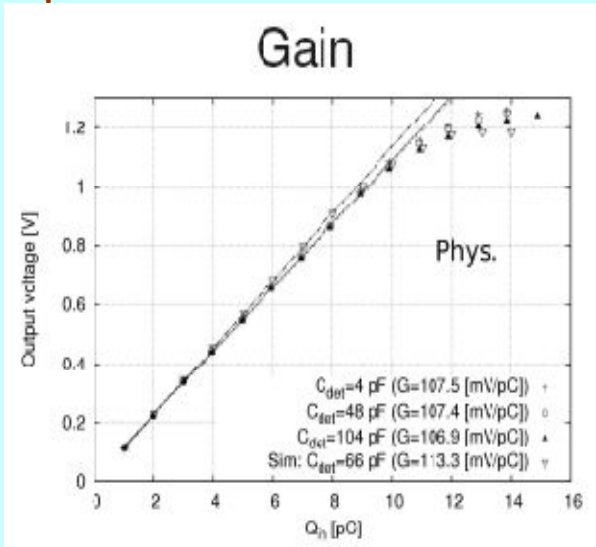
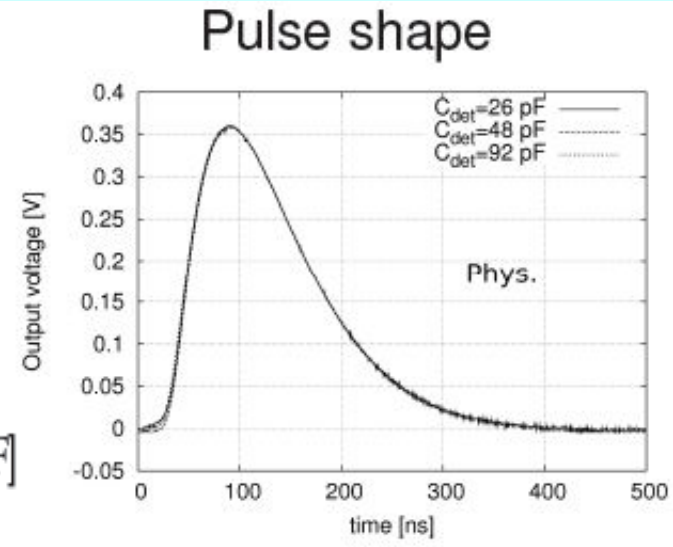
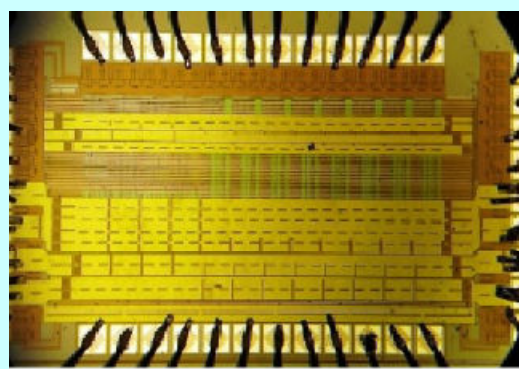


Design of a 32 channel prototype currently ongoing, First prototypes (smaller number of channels) will be ready in December

- Dual gain charge amplifier  
switched capacitor filter
- ADC ASIC 10 bit successive approximation ADC (3.25 MS/s)
- Additional 8 bit low latency output (beam diagnostics)

# ASIC development, LumiCal

## 8 channel preamplifier ASIC, lab tests, matches the requirements



- $Noise_{phys}[aC] = 522 + 2.08 \cdot C_{in}[pF]$
- $Noise_{cal}[aC] = 48 + 4.65 \cdot C_{in}[pF]$

**Power consumption per channel: 8.9 mW**

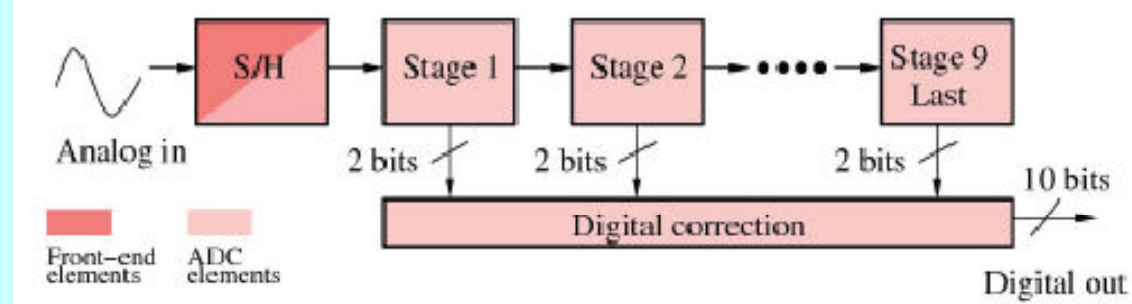
**Ready for tests with sensors!**

Mode	Gain [mV/fC]	Noise@50pF [fC]	Linearity [pC]	Rate [MHz]	Crosstalk [%]
Physics	0.107	0.62	10	3	≈1
Calibration	≈20	0.28	0.035	2.5	≈0.1

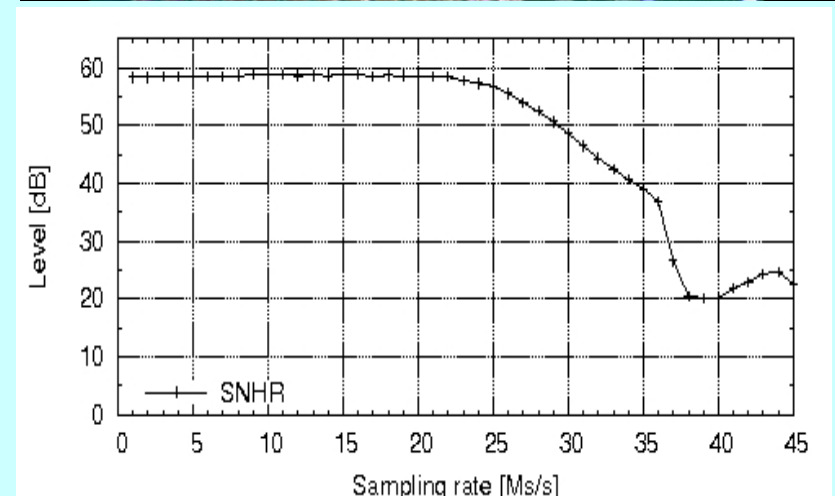
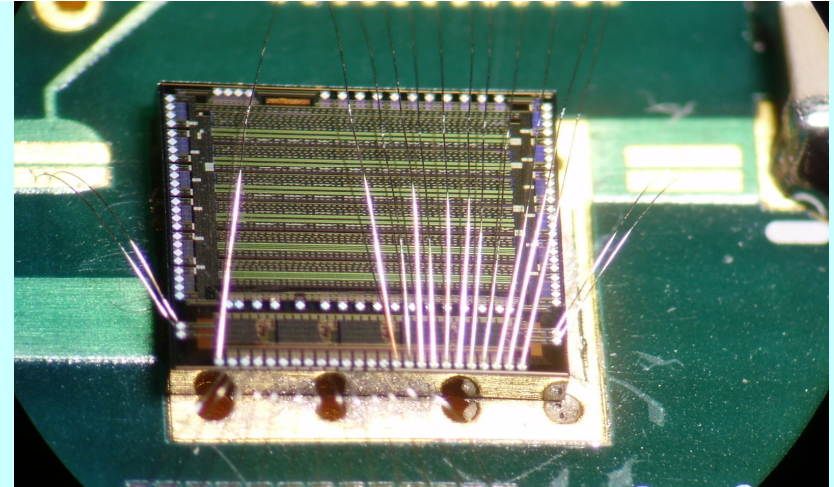
- Design of assembly with a sensor
- Test in the lab and testbeam
- Redesign after these tests

# ASIC development, LumiCal

One channel ADC ASIC  
(differential pipeline architecture)

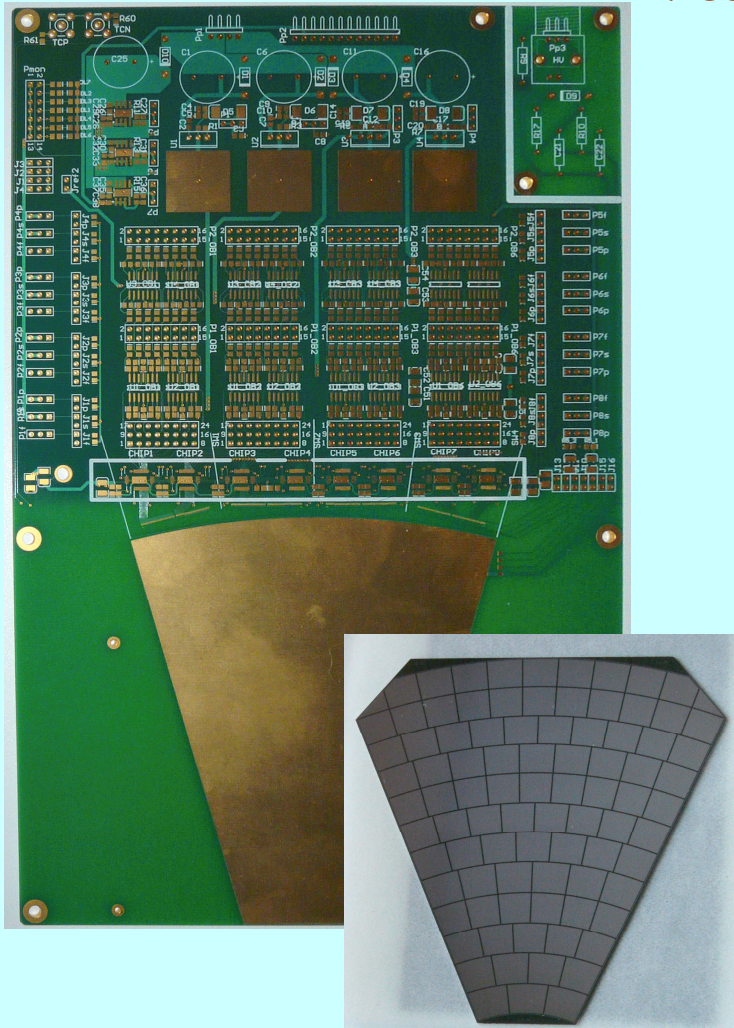


- New 10 bit ADC fully functional
- Stable operation up to 25 MHz
- Good static performance (DNL, INL, ENOB)
- Dynamic measurements just started
- Clock and power switching tests
- Preparation of a multichannel version



# System Test in a beam

## Readout/Fanout of sensors

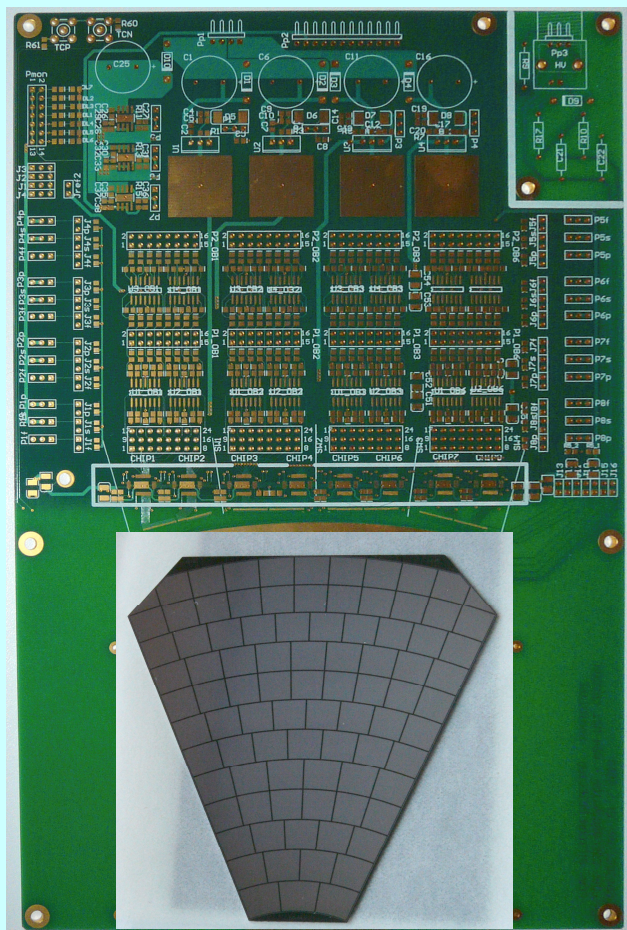


- fine pitch PCB, (100...200 $\mu$ m for current few channel FE chips)
- flexible PCB to be designed. matters of crosstalk & capacitive load
- wire bonding or bump bonding to pads (wire bonding needs  $\sim$  3mm gap between absorber tiles; conductive glueing also discussed)
- wire bonding to FE chip
- Silicon and GaAs sensor samples

Template of a readout board, to be instrumented with FE ASICS

# System Test in a beam

## Readout/Fanout of sensors



- state of the art fine pitch PCB, (100...200 $\mu$ m for current few channel FE chips)
- matters of crosstalk & capacitive load
- wire bonding or bump bonding to pads (wire bonding needs  $\sim$  3mm gap between absorber tiles; conductive glueing also discussed)
- wire bonding to FE chip
- Silicon and GaAs sensor samples
- Beam test planned 2010

Template of a readout board, to be instrumented with FE ASICs

# Conclusions

- Investigation of the radiation hardness of GaAs, diamond and Sapphire up to 10 MGy. No baseline material for BeamCal so far
  - diamond: too expensive
  - GaAs : rad. tolerant up to 1 MGy
  - Sapphire: studies just started
- Prototyping of Si sensors for Lumical successful
- FE ASICS ready for test with sensors
- System test in preparation
- ADC ASICS - prototypes under test

Goal up to 2012: demonstrate the functionality of a sensor plane sector